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K. Jones
10/18/02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

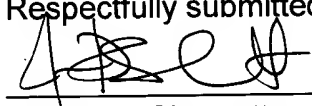
Application Serial No. 09/512,968
Filing Date February 24, 2000
Inventor David R. Hembree
Assignee Micron Technology, Inc.
Group Art Unit 2858
Examiner V. Nguyen
Attorney's Docket No. MI22-1363
Title: Electronic Device Workpiece Processing Apparatus and Method of Communicating
Signals Within an Electronic Device Workpiece Processing Apparatus

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. No admission is made regarding whether all the submitted references are prior art.

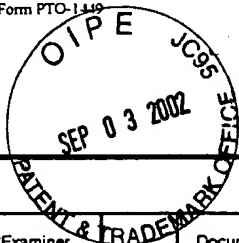
Dated: 9/3/03

Respectfully submitted,


James D. Shaurette
Reg. No. 39,833

EV182664188

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
M122-1363SERIAL NO.
09/512,968LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)APPLICANT
David R. HembereFILING DATE
February 24, 2000GROUP
2832

U.S. PATENT DOCUMENTS

*Examiner Initials		Document Number	Date	Name	Class	Subclasses	Filing Date If Appropriate
	AA	3,440,407	4/22/69	Golstos et al.			
	AB	3,614,345	10/19/71	Quinn			
	AC	3,683,306	8/8/72	Bulthius et al.			
	AD	4,332,081	6/1/82	Francis			
	AE	4,518,944	5/21/85	Faris			
	AF	4,703,555	11/3/87	Hubner			
	AG	5,141,334	8/25/92	Castles			
	AH	5,347,869	9/20/94	Shie et al.			
	AI	5,406,109	4/11/95	Whitney			
	AJ	5,436,646	7/25/95	McArthur et al.			
	AK	5,446,437	8/29/95	Bantien et al.			

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclasses	Translation	
							Yes	No
	AL	2336778	7/1977	France				
	AM	56-12521	2/1981	Kobayashi, Japan				
	AN	2-268462	11/1990	Yamanishi, Japan				
	AO							
	AP							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

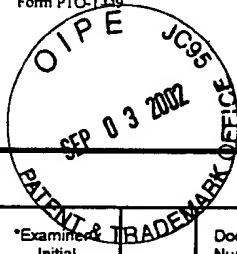
	AR		"Application Guide Temperature Sensors", Watlow Electrical Manufacturing Company Catalog, pp. 775-778, 1992/1993.
	AS		"In-Situ survey System of Resistive and Thermoelectric Properties of Either Pure or Mixed Materials in Thin Films Evaporated Under Ultra High Vacuum", Lechevallier, LeHuerou, Richon, Sarrau, & Gouault, J. Phys. III France, Vol. 5, pp. 409-418, 04/95 (Abstract only).
	AT		"Temperature Metrology for CD Control in DUV Lithography", Jeffrey Parker and Wayne Renken, pp. 111-112, 114, 116, 09/17/97.

EXAMINER

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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form PTO-1119

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MI22-1363SERIAL NO.
09/512.968LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)APPLICANT
David HembreeFILING DATE
February 24, 2000GROUP
2858

U.S. PATENT DOCUMENTS

*Examiner Initial	Document Number	Date	Name	Class	Subclas s	Filing Date If Appropriate
	AA	5,812,574	3/18/97	Summerfelt et al.		
	AB	5,719,333	2/17/98	Hosoi et al.		
	AC	5,831,333	11/3/98	Malladi et al.		
	AD	5,919,548	7/6/99	Barron et al.		
	AE	5,551,283	9/3/96	Manaka et al.		
	AF	5,492,011	2/20/96	Amano et al.		
	AG					
	AH					
	AJ					

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclas s	Translation	
						Yes	No
	AK						
	AL						
	AM						
	AO						

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

AP	"NTC and PTC Thermistors"; http://www.thermodisc.com/ntcptc.html ; 1/7/98; 2 pages.
AR	"DI-5B35 Linearized 4-Wire RTD Input"; http://www.dataq.com/di5b35.html ; 1/7/98; 2 pages.
AS	"RTD"; http://www.mtisensors.com/rtds.html ; 1/7/98; 3 pages.
AT	"Low Cost Thermal-Ribbon (TM) uses thin film RTD"; http://www.minco.com/s17624nr.html ; 1/7/98; 1 page.
AU	"Silicon Processing for the VLSI Era"; Volume 1 - Process Technology; Second Edition; S. Wolf et al.; 2000; pps 22-25 and pps. 841-845.

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DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.